

Flexible Nonvolatile Memory



Snehil Verma

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Overview

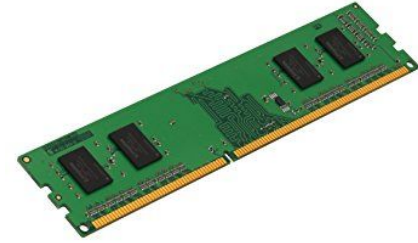
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Motivation

With the advent of healthcare technology, IoT, and big data applications, the need for memory with the following characteristics increased:

- Ultra-dense
 - Ultra-low-power
 - Robustness to environmental variations (reliability)
-

IoT -> Fully flexible electronic system



- Processing units - CPU
- The main memory - RAM
- Storage - NVM



Requirements

In order to replace traditional mechanical hard disks with solid-state storage devices, a fully flexible electronic system will need two basic devices:

- Transistors: Used for logic operations and gating memory arrays
- Nonvolatile memory: Required for storing information in the main memory and cache storage.

Overview: Mainstream Design Approaches

All-organic systems

Both devices and substrates are made up of organic materials.

Hybrid systems

Inorganic electronic devices are transferred onto an organic substrate

SOI substrate

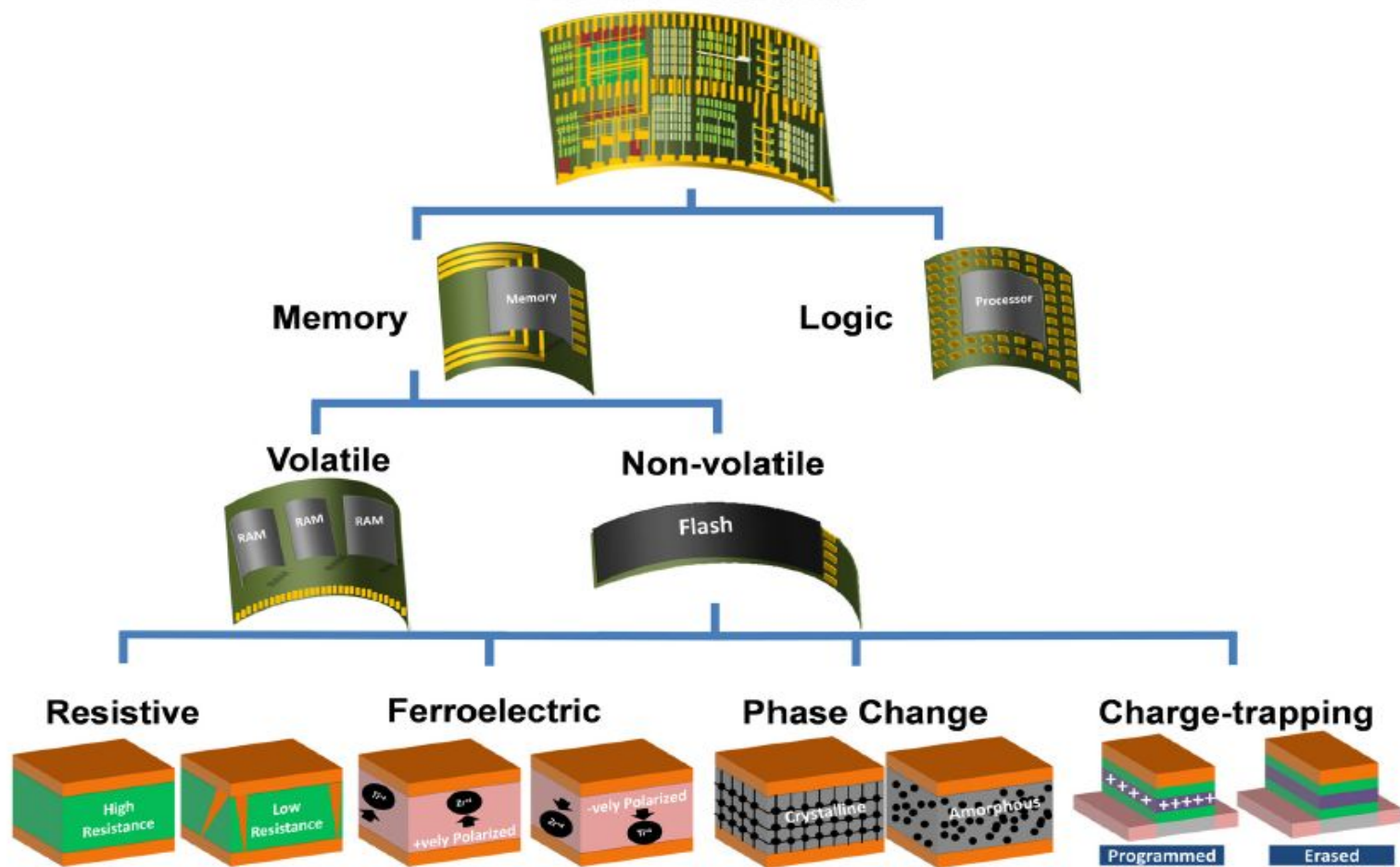
Use silicon-on-insulator (SOI) substrates, and controlled spalling technology to peel-off thin semiconductor layers.

Overview: Emerging NVM

- Resistive RAM (ReRAM)
- Flash memory (floating gate and charge trapping)
- Phase change RAM (PCRAM)
- Ferroelectric RAM (FeRAM)

Benefits of fast switching, low-operation voltage, and ultra-large-scale-integration (ULSI) densities.

Flexible Electronics



Materials used for designing NVM

0-dimensional

- Gold nanoparticles (NPs)
- Black phosphorus quantum dots (QDs)
- Silicon QDs

1-dimensional

- ZnO nanowires
- Si nanowires
- Carbon nanotubes (CNTs)

2-dimensional

- Graphene
- Graphene oxide
- MoS₂
- ZnO
- Hydrated tungsten trioxide (WO₃·H₂O) nano-sheet

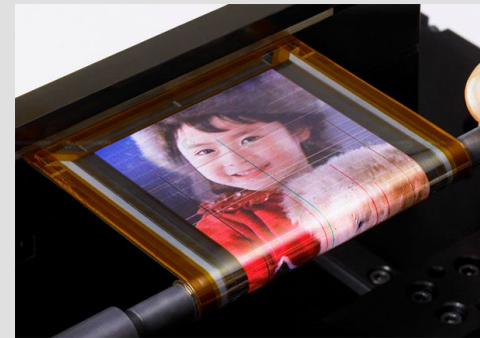


Samsung



Semiconductor Industry: Artificial Skin, Display

Sony

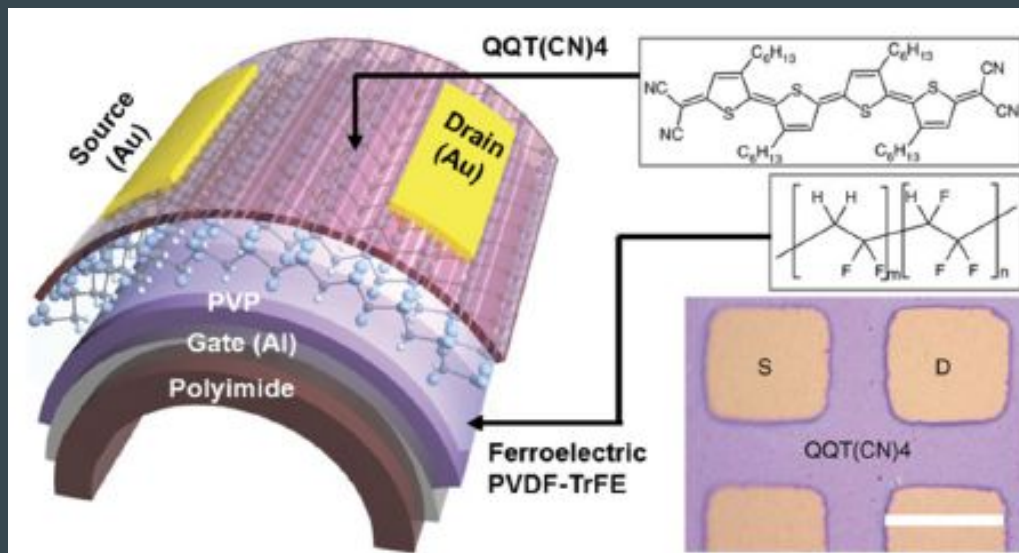


Approaches for Making Flexible Devices

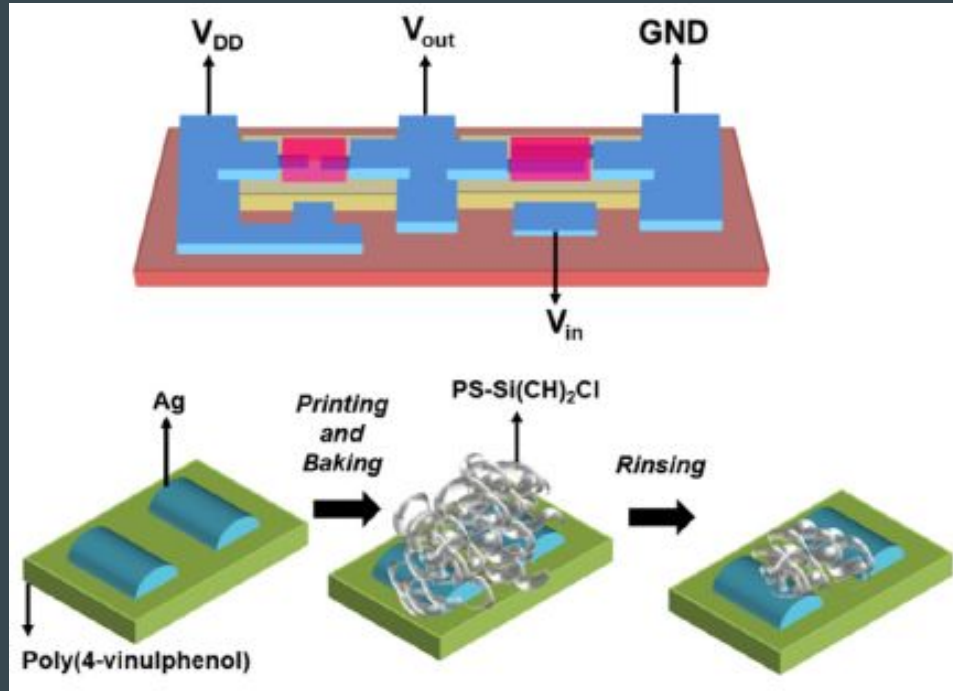
All-Organic Approach

- Polymeric semiconductors as channel materials.
- Polymeric ferroelectrics for nonvolatile storage.
- Thick, durable insulating polymers to support the flexible substrate.

All-organic deposited NVM



All-Organic Approach



Inkjet-printed organic inverter on a plastic substrate

All-Organic Approach

Challenges

Performance:

- The highest reported mobility more than 20 times lower than silicon (exception of $43 \text{ cm}^2/\text{V.s}$ peak hole saturation mobility reported by Yongbo Yuan et al. [3]).
- Reliability
- Thermal stability [4]

Advantages

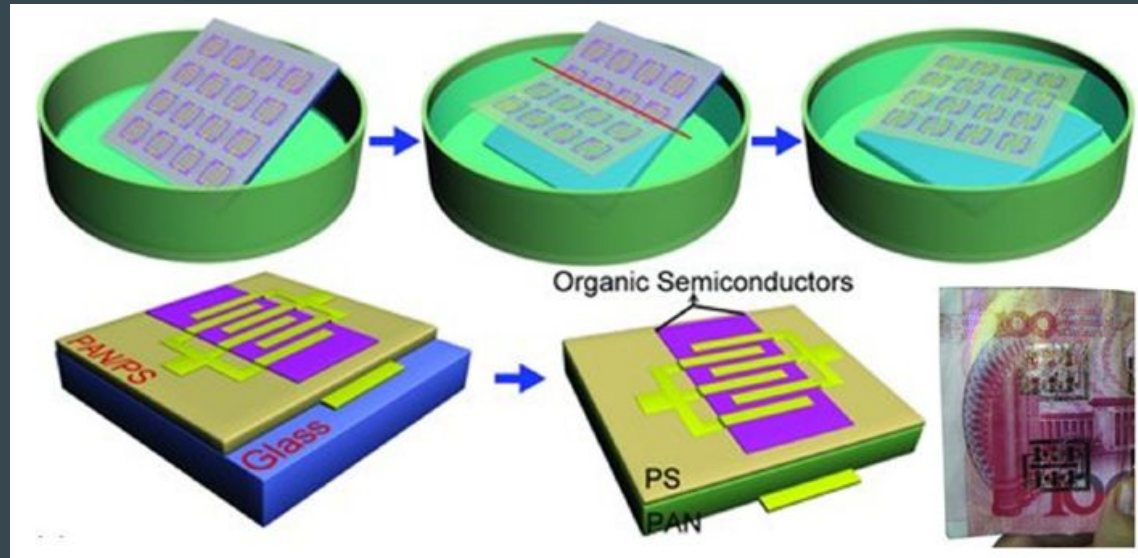
- Low cost
- Flexibility - AMOLED display

Hybrid Systems Approach

Use both organic and inorganic materials.

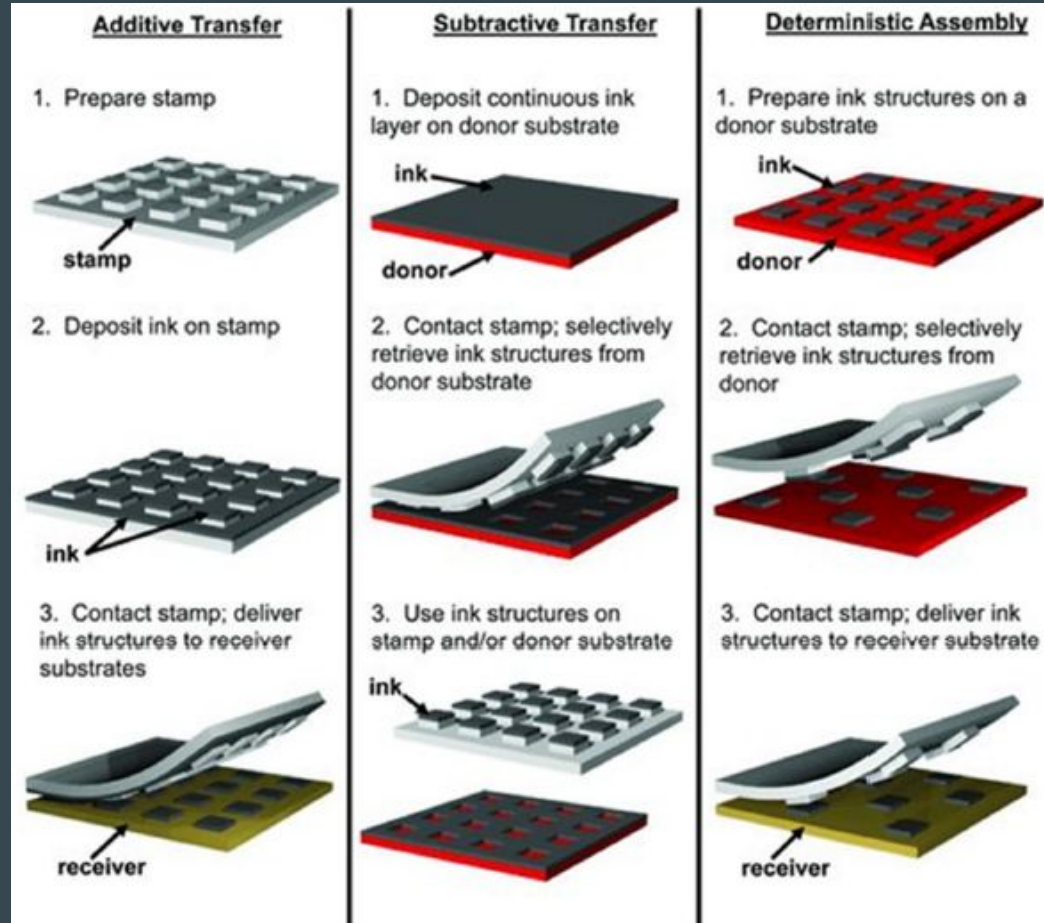
- More versatile.

Generic transfer technique, where devices are fabricated on a specific rigid substrate and then transferred to one that is flexible

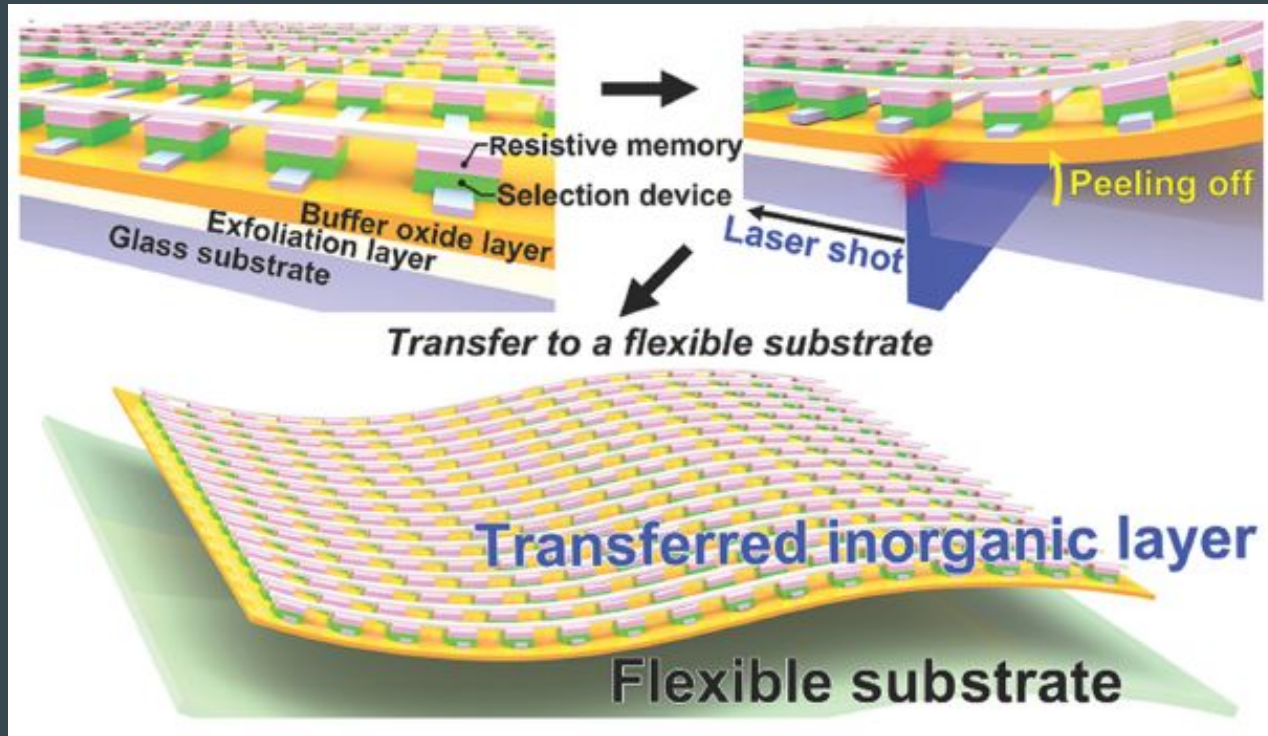


Hybrid Systems Approach

Three modes of transfer printing



Hybrid Systems Approach



Fabricating flexible crossbar-structured memory on a plastic substrate via the laser lift-off transfer method

Hybrid Systems Approach

Challenges

- Extra non-conventional transfer steps.
- Low yield

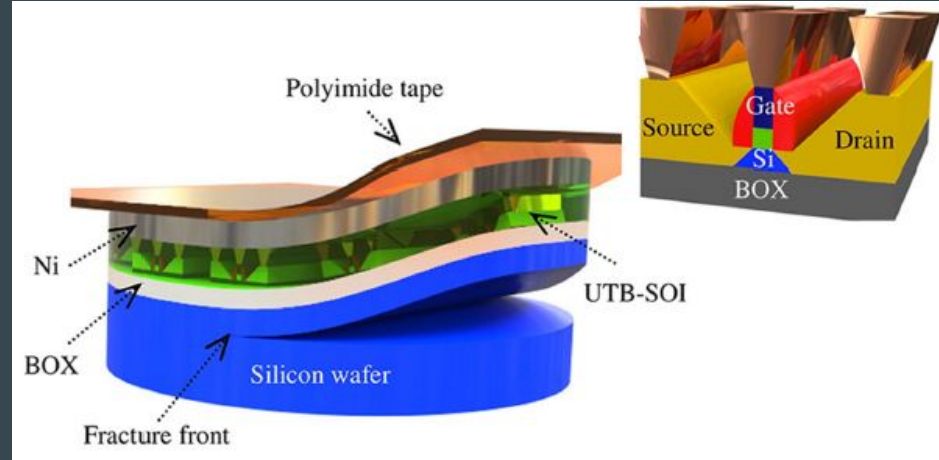
Advantages

- High performance

Spalling Technology

Use stressor layers to initiate fracture-modes in SOI and semiconductor substrates.

- Deposit a Ni stressor layer that is abruptly discontinued near one edge of the wafer where a crack in the mono-crystalline silicon (Si) is to be initiated by applying a force [9, 10].
- Before the force is applied, polyimide tape is added to support the flexible peeled layer bearing ultra-thin body devices.



Spalling Technology

Challenges

- Extra deposition and complex tuning of a stressor material with a specific thickness followed by etching are required
- Once the crack has been initiated, the peeling-off process requires high dexterity that is not suitable for mass production

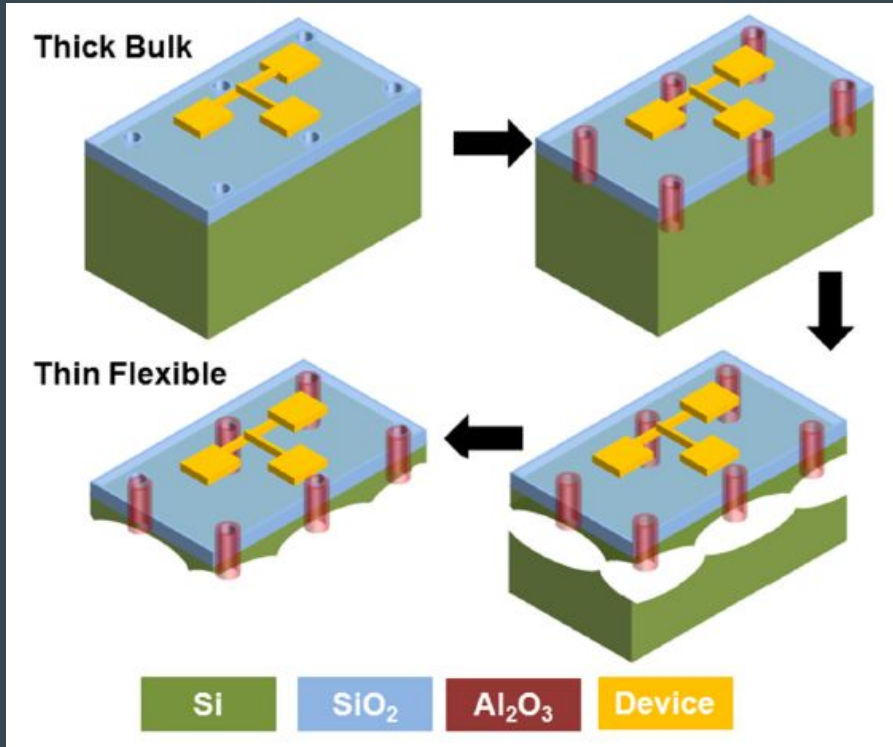
Complementary Transfer-free Inorganic Approach

Inverse proportionality between the material's thickness and flexibility.

- High performance
- Reliability
- ULSI density
- Low cost

$$\textit{Flexibility} \propto t^{-3}$$

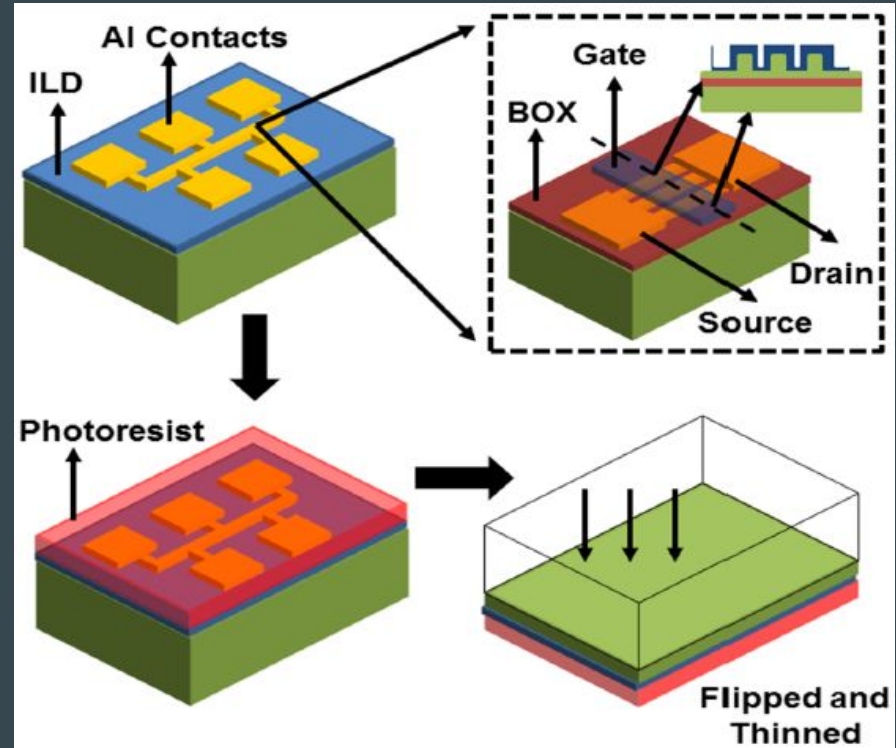
Complementary Transfer-free Inorganic Approach



Silicon-flexing technique (Device first approach)

Complementary Transfer-free Inorganic Approach

Soft-etch back approach



Fracture Strength

Most common method: three-point bending test.

- Based on the application's required bending radius, the thickness of the flexible silicon substrate must be adjusted such that the applied stress is lower than the fracture stress.
- Eg. : the minimum bending radius that would cause fracture stress for a 50- μm thick flexible silicon substrate is ~ 3 mm

NVM Operational Principles and Architectures

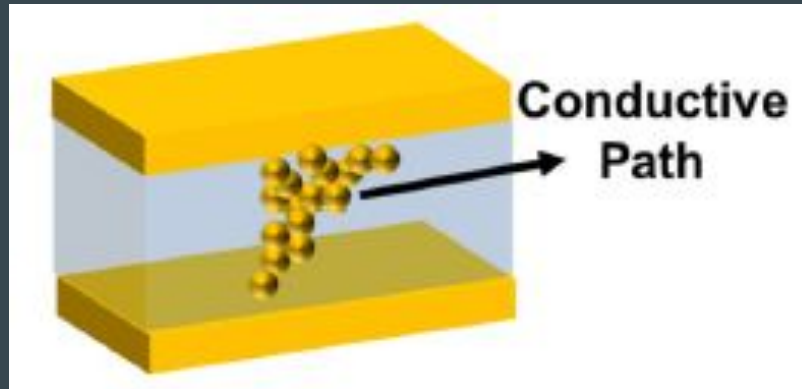
NVM Operational Principles

- Capable of storing information over long periods of time (~10 years is the industry standard)
- Retain information even when no power is supplied.

Leading Flexible NVM technologies

Resistive RAM: ReRAM (Memristor)

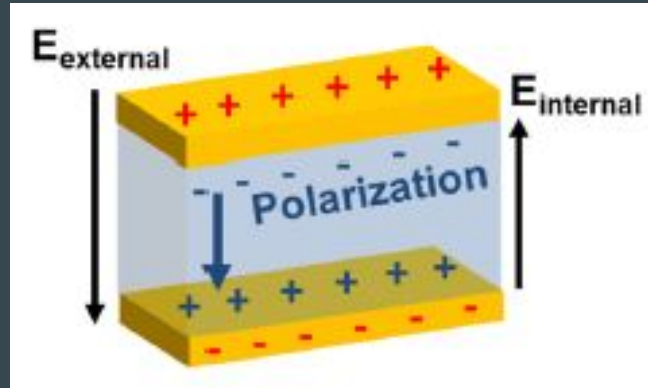
- A resistive oxide is sandwiched between two metallic layers.
- The resistance of the oxide changes with applied “set” and “reset” voltage pulses.



Leading Flexible NVM technologies

Ferroelectric RAM: FeRAM

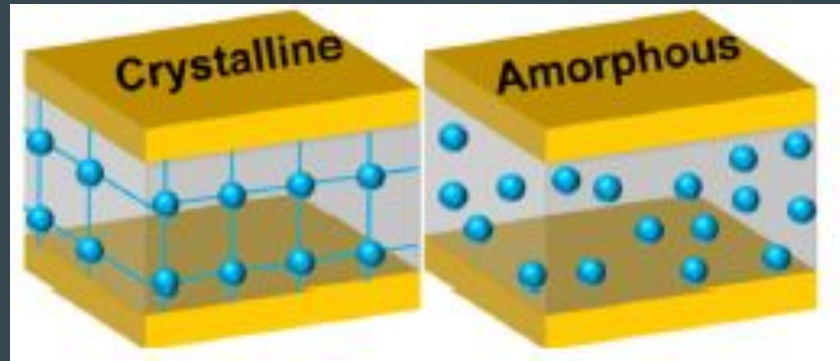
- A ferroelectric material has two possible polarization states inherent from its crystalline structure.
- Applying write/erase voltage pulse switches for positive to negative polarization states.



Leading Flexible NVM technologies

Phase change RAM: PCRAM

- Current or laser pulses are applied to change the phase of a material from crystalline (low resistance) to amorphous (high resistance) and vice versa at a localized space, which changes the material's electrical and optical properties.



Leading Flexible NVM technologies

Flash memory (floating gate (FG))

- Similar structure as a field effect transistor (FET), except that its gate dielectric is split into three layers.
 - Tunneling oxide
 - Embedded conductor layer - floating gate
 - Blocking oxide
- When a programming voltage is applied, carriers tunnel from the channel to the floating gate.



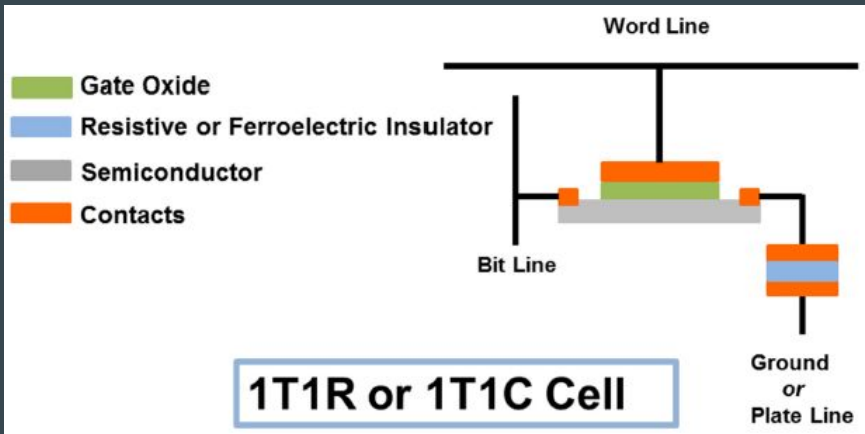
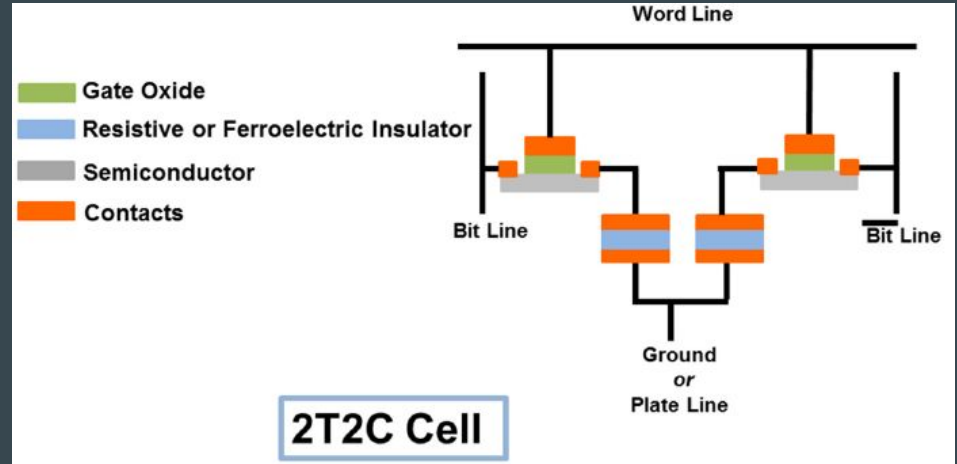
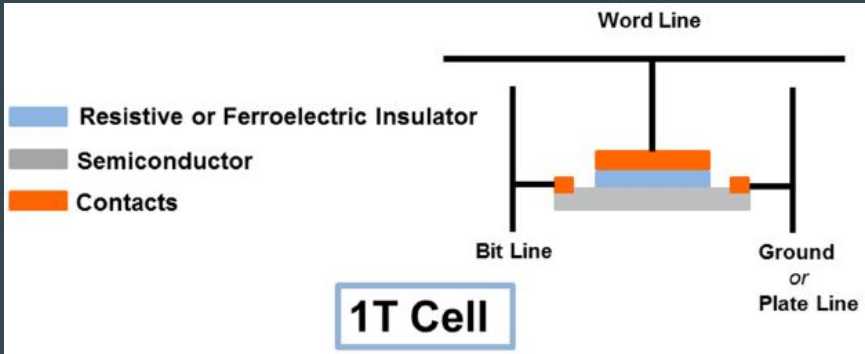
Leading Flexible NVM technologies

Flash memory (charge trapping (CT))

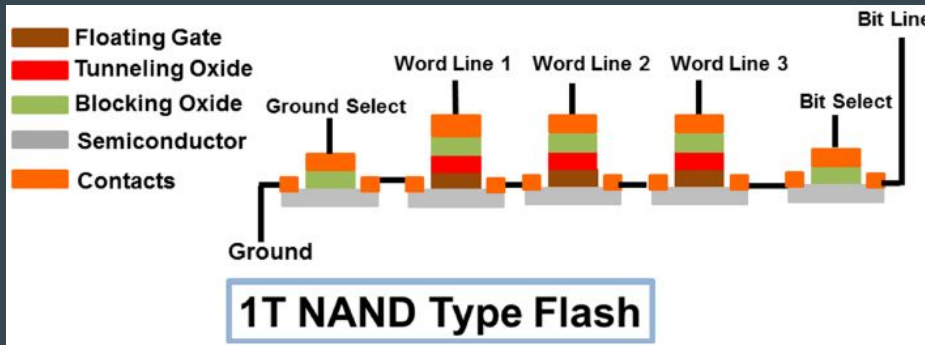
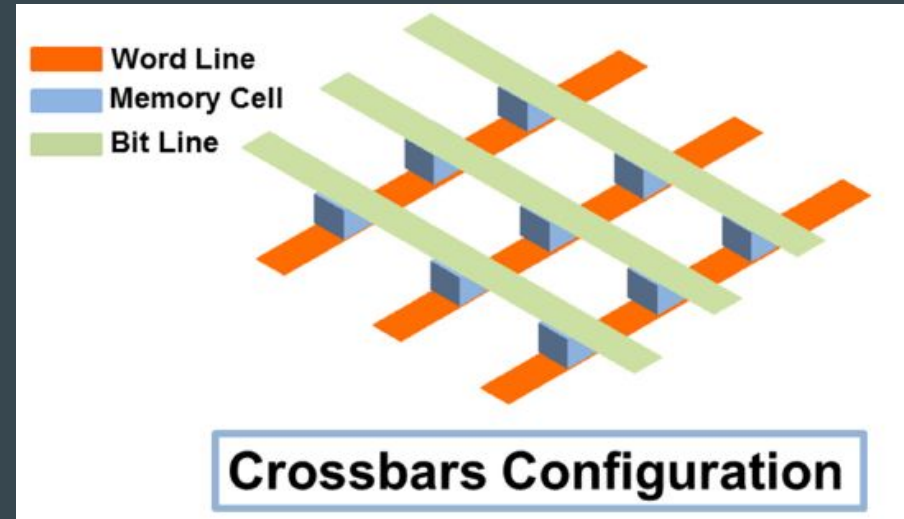
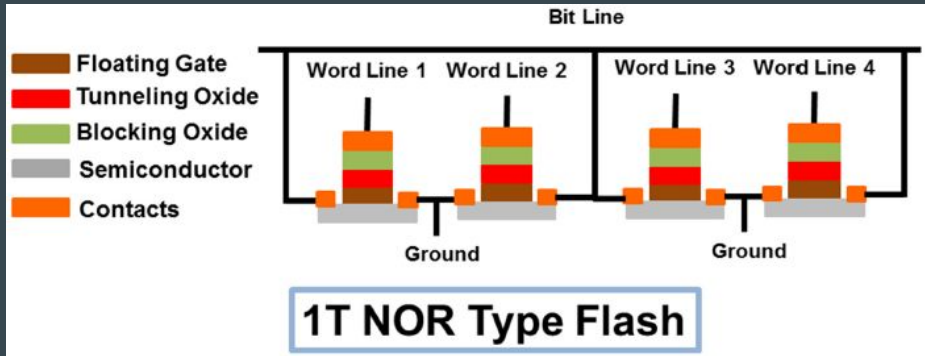
- The charge trap flash replaces the floating gate (a conductor layer) with an insulating layer.



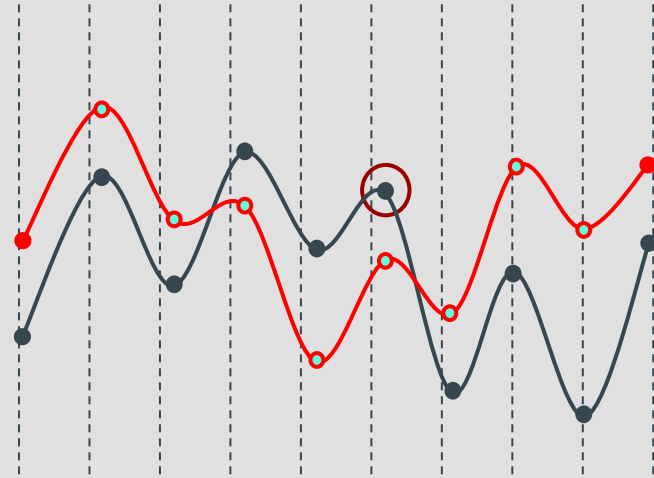
NVM Architectures: Memory Cell design



NVM Architectures: Major arrangements



Idea of Numbers: Flexible NVM Technologies



Figures of Merit

- Form Factor (F^2)
 - Density
 - Cost (\$/bit)
 - Endurance
 - Retention
 - Operation voltage
 - Speed
 - Memory window
-

Flexible ReRAM

- Report for 10 nm × 10 nm ReRAMs [14].
- S. Jo et al. experimentally demonstrated that CMOS neurons and memristor synapses in a crossbar configuration can support synaptic functions [15].
- Interesting work using inorganic flexible substrate (Al foil) with organic cellulose nanofiber paper enabled achieving the lowest reported bending radius for ReRAM (0.35 mm) and lowest operating voltage (± 0.5 V) [21].

Flexible FeRAM

- In general, FeRAMs have superior endurance and low variability, which represent critical challenges for state-of-the-art redox memristive memories [22].
- Rigid ferroelectric random access memories (FeRAM) have already made a great leap by their introduction to the market; hence, it is a relatively mature technology compared to other emerging NVM technologies.
- Commonly used ferroelectric material in FeRAM is lead zirconium titanate ($\text{Pb}_{1.1}\text{Zr}_{0.48}\text{Ti}_{0.52}\text{O}_3$ —PZT).
 - high switching speed ~ ps for material switching and 70ns for actual arrays (parasitic capacitances)
 - low cost per bit
 - low operation voltage - 1.5V
 - Read/Write Cycles $> 10^{15}$
 - Retention > 10 years at 85 °C

Flexible PCRAM

- In general, PCRAMs have high switching transition speed. Eg.: Flexible PCRAM on polyimide required a 30 ns pulse to switch.
- Highly localized regions of phase change that enables ultra-high integration densities. Hong et al. reported phase-change nano-pillar devices with the potential of reaching up to tera bit/squared inch densities on flexible substrates.
- Yoon et al. demonstrated a 176 Gbit/square inch PCRAM, the highest reported density on a flexible substrate.
- The highest reported bending cycles endurance (1000 bending cycles) and yield (66%) for flexible PCRAM was reported by Mun et al., in 2015.

Flexible Flash

- Most mature NVM technology in today's market.
- Current flexible flash memories have reported operation voltages ranging from ± 5 to ± 90 V with minimum channel length dimensions of 2- μm [19].
- Nonetheless, good bendability has been achieved up to 5 mm for 2000 bending cycles, an endurance of 100,000 cycles, and a retention ability of 10^6 s.

Comparison of the Best

	Flexible ReRAM	Flexible FeRAM	Flexible PCRAM	Flexible Flash
Form Factor (F ²)	2	1	--	2
Cell Dimensions (μm)	10 × 20 channel	20 × 20	0.035 diameter	2 channel length
Endurance (cycles)	10 ⁶	10 ⁹	100	10 ⁵
Retention (s)	5 × 10 ⁶	10 ⁵	10 ⁴	10 ⁶
Operation voltage (V)	-0.5	-3	1.8	-5 to +5
Speed (ns)	50	500	30	100
Memory window (V)	4	35	--	15

Future Prospects?

Thank You

Questions?

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